

ABSTRACT

A large-size glass substrate, from which a photomask
5 substrate is formed, is prepared by processing a large-size
glass substrate stock by (1) a flattening removal quantity
based on height data of the substrate stock in the vertical
attitude plus a deformation-corrective removal quantity. The
deformation-corrective removal quantity is calculated from
10 (2) a deflection of the substrate stock by its own weight in
the horizontal attitude, (3) a deformation of the photomask
substrate caused by chucking in an exposure apparatus, and
(4) an accuracy distortion of a platen for supporting a
mother glass.